

Digitally Controlled Crystal Oven

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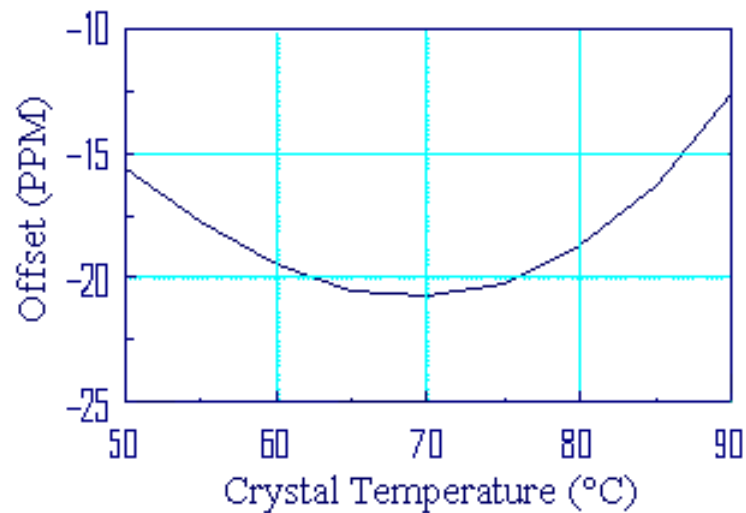
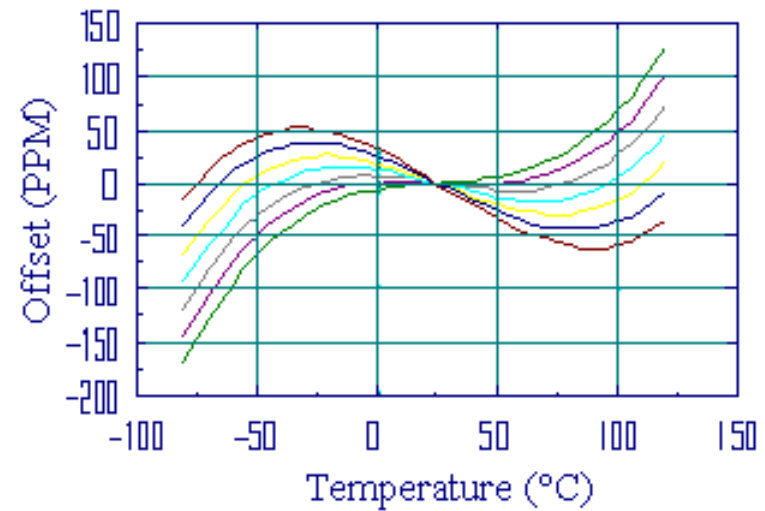
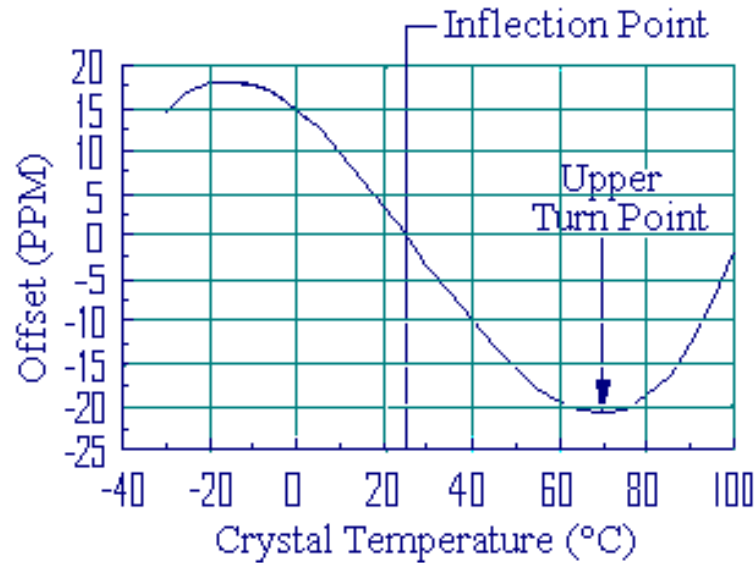
Attributes of widely-used frequency references

	Description	Stability/ accuracy	Price	Power	Warm-up time to rated operation	Applications
XO, VCXO	Crystal oscillator	10^{-4} - 10^{-5}	<\$1	50mW	<10s	Watches, phones, TV, PC, toys
TCXO	Temperature compensated crystal oscillator	10^{-5} - 10^{-6}	<\$10	50mW	<10s	Wireless, GPS
OCXO (AT-cut)	Ovenized Crystal oscillator	10^{-7} - 10^{-9}	<\$200	600mW (peak)	<100s	Instruments, telecom, radar, satcom
Rubidium	Rb Frequency Standard	10^{-10} - 10^{-12}	<\$5000	20W	<300s	SONET/ SDH, calibration, test, GPS base stations
Cesium	Cs Frequency standard	10^{-11} - 10^{-12}	<\$50,000	30W	<2000s	SONET/ SDH, calibration, test

Ovenized crystal oscillators (OCXOs)

- Stability of low-end (10^{-8} to 10^{-9}) frequency standards
- Reduced steady-state power consumption
- Reduced warm-up time
- Priced at \$50, much of the cost is in manufacturing process and tuning/ calibration (rather than raw material)
- Our focus is on reducing tuning/ calibration costs by replacing analog components with digital technology

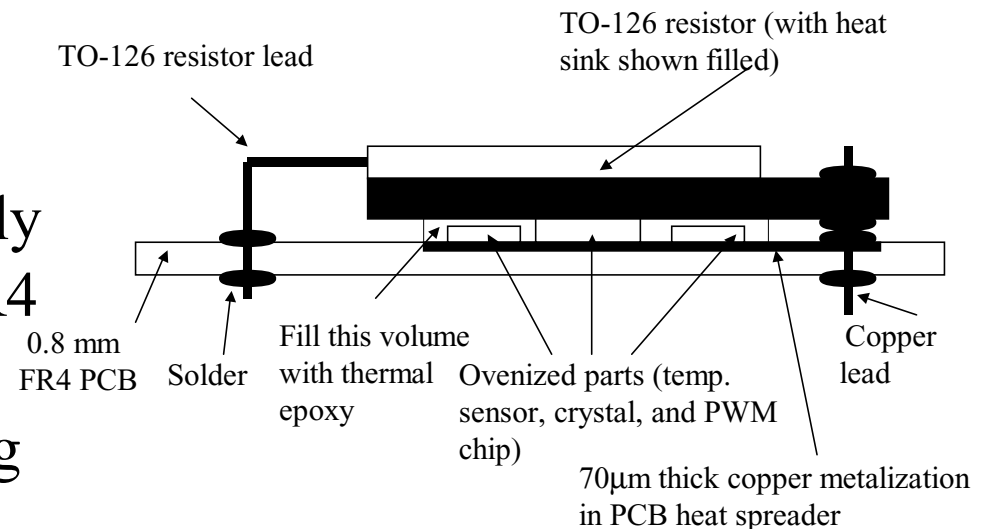
Temperature vs. Frequency



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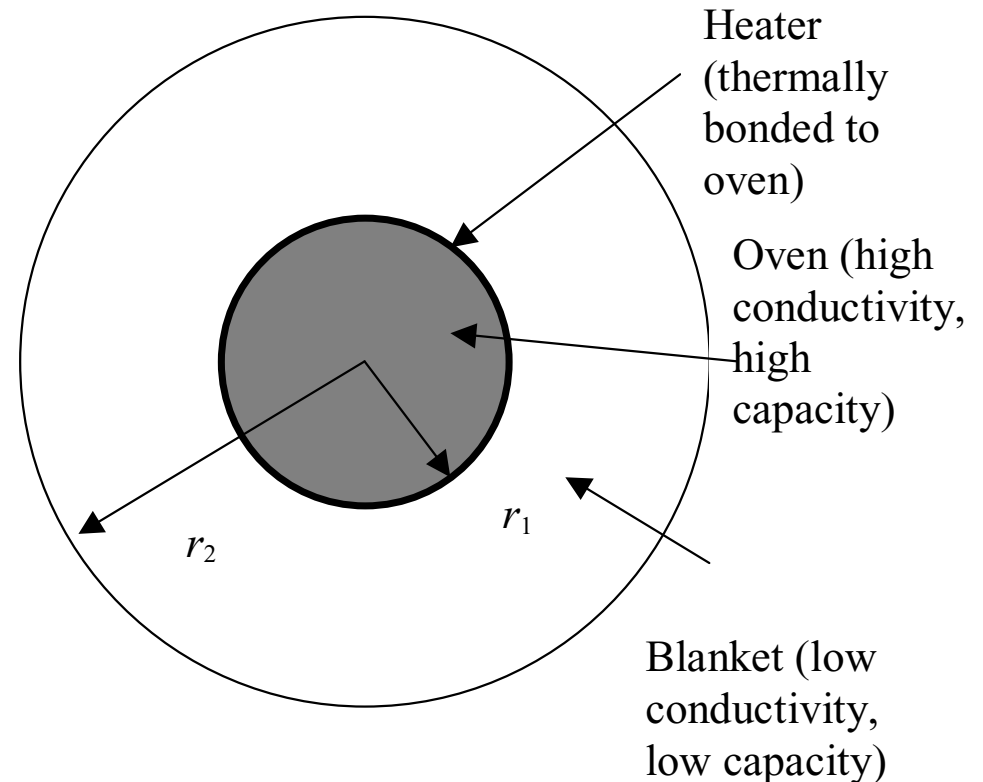
Use mass-produced oven materials

- Standard power resistors (rather than thermofoil heaters)
- Thermal mass of (electrically isolated) metalization of FR4 PCB heat spreader may be increased by nickel cladding
- Copper lead/ solder provides thermal connection from heater to metalization



Relative oven/ blanket dimensions

- Oven $C \propto r_1^3$
- Oven R (wrt ambient) $\propto (r_2 - r_1) / r_1^2$
- Oven $RC \propto r_1 \cdot (r_2 - r_1)$
- Maximized at $r_1 = r_2 / 2$ (independent of oven/ blanket materials!)
- At this r_1 (for a given r_2), high frequency variations of ambient temperature are filtered out
- Similarly, heater $RC \propto r_1$
- (Oven lag/ heater lag) $\propto (r_2 - r_1)$. Increase for better control.
- Steady-state heater power $\propto (\theta_h - \theta_a) \cdot r_1^2 / (r_2 - r_1)$

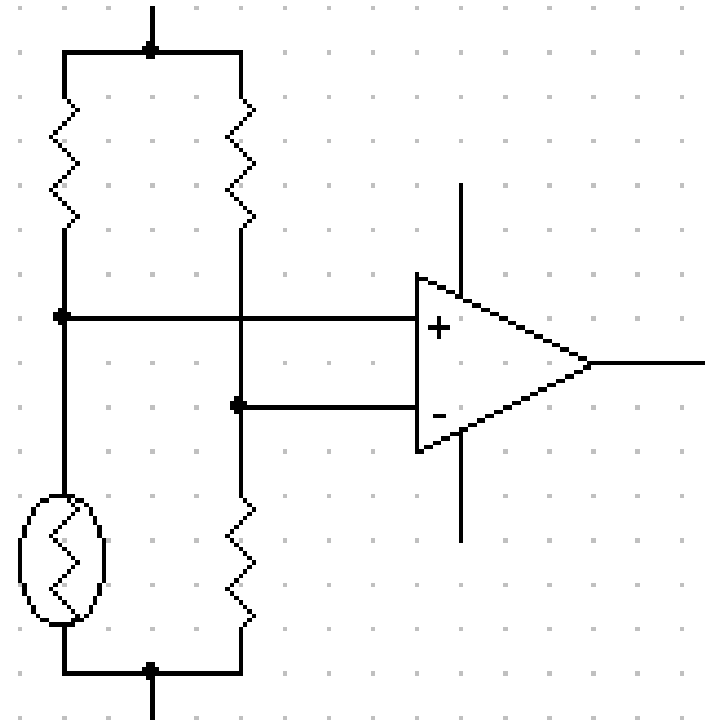


In practice, reducing the oven size based purely on mechanical considerations, may reduce oven controllability because of self heating!

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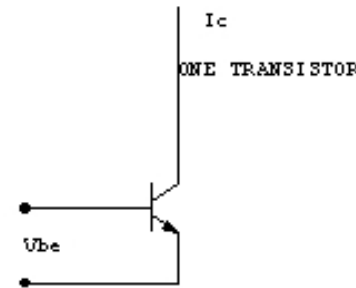
Traditional Oven Controller

- Use thermistor (resistor with –ive tempco) bead, bonded to heat sink, in otherwise resistive bridge
- Aging effects behavior of all components, but most severe is the drifts of the OP Amps (usually 3) in controller
- Need to tune controller before encapsulation (i.e., assumes that this is a repeatable process)
- Tuning potentiometers are effected by aging/ shock

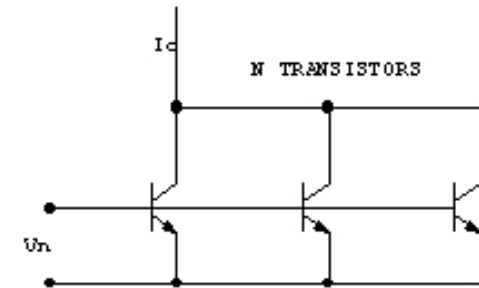


Semiconductor Temperature Sensor

- Typical non-linearity: $\pm 0.1^\circ\text{C}$ over -40°C - 105°C
- $\pm 0.5^\circ\text{C}$ maximum error at a given temperature
- Drift with aging $< 0.2^\circ\text{C}$ over 10,000 hours operation

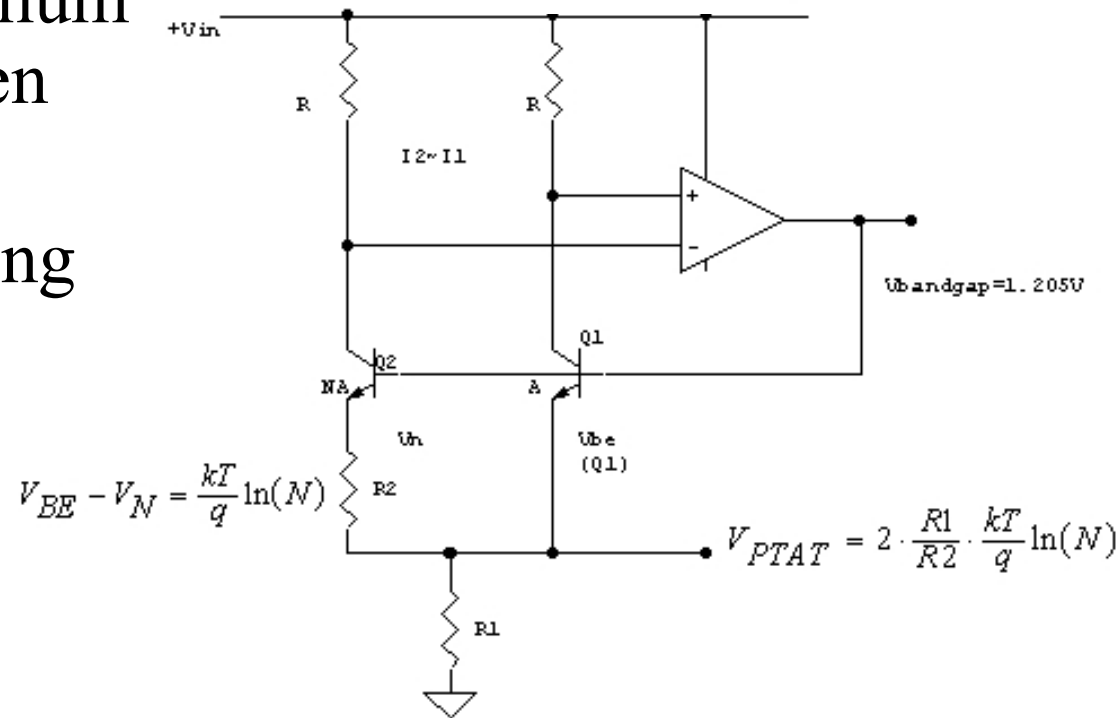


$$V_{BE} = \frac{kT}{q} \ln\left(\frac{I_c}{I_s}\right)$$



$$V_N = \frac{kT}{q} \ln\left(\frac{I_c}{N \cdot I_s}\right)$$

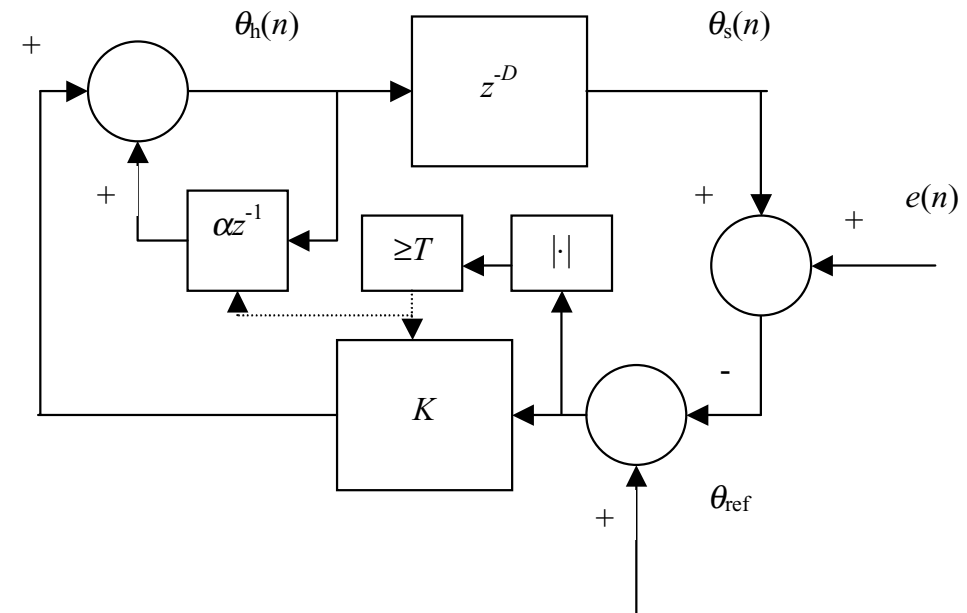
$$V_{BE} - V_N = \frac{kT}{q} \ln(N), \text{ Independent of } I_c, I_s$$



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Proportional plus derivative controller with feed-forward

- Feed-forward to compensate for oscillation at thermal lag
- Lack of integral term (which would add to thermal lag and be prone to “wind-up”) gives rise to a steady state “droop”
- Derivative term expands proportional range and reduces overshoot (which may harm electronic circuits over time)
- Can control to 0.0625°C



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Compensation for supply voltage variations

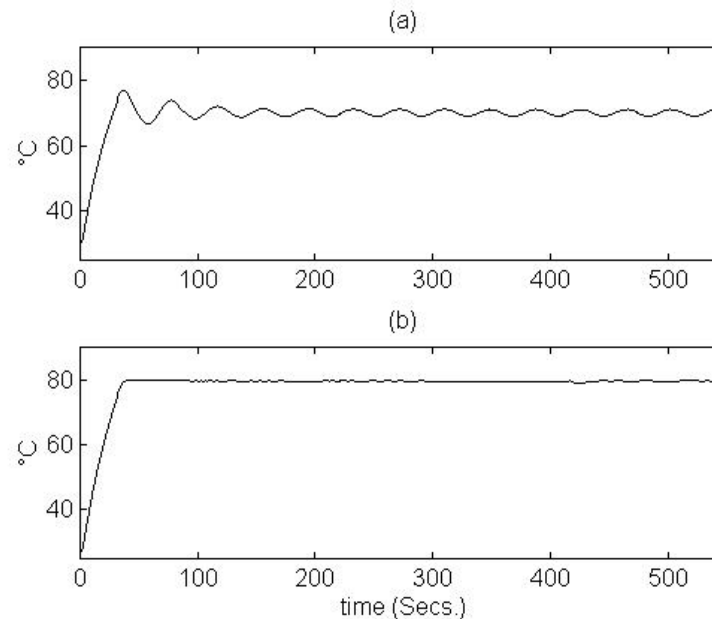
- Regulation adds uncontrolled hot-spot in enclosure
- $\rho(n) = \rho(n-1) + \rho(n-1) \cdot [V^2(n-1) - V^2(n)] / V^2(n)$
- Executed frequently (compared to the oven time constant)
- Anti-aliasing filter to reject high-frequency noise
- Use an inexpensive PWM chip to sense supply voltage

Implementation

- 8-PIN SOIC low-profile PIC12CE519-04I/SN micro-controller
- 16-byte EEPROM stores temperature/ frequency set-points and controller constants
- No interrupts!
- 8-bit timer has insufficient resolution to implement PWM (requires 16-bit accuracy)
- Use quantization to 8-bits and first order quantizer feed-back
- Communicate temperature to PC (every 1.2 seconds) and allow changes to set-points (temperature/ frequency/ controller constants)
- Use digital potentiometer to set varactor diode bias (for frequency tuning)

Oven response tuning

- Variant of the Ziegler-Nichols method
- Set $K_d=0$, $\alpha=1$ and then increase K to K_u , where continuous cycling, with period P_u seconds, around a lower-than nominal temperature occurs (Fig. a)
- K , K_d and α are set to $0.75K_u$, $4P_u/\Delta T$ and $1-(\Delta T/P_u)$ respectively (ΔT is sampling time in seconds).
- For example oven, $K_u=31$, $P_u=36$ seconds; setting $K=24$, $K_d=128$ and $\alpha=31/32$ yields a rise time and settling time of 41 and 93 seconds respectively. Droop is 0.28°C . The overshoot from the drooped temperature is 0.41°C .
- Then set temperature to desired target (response in Fig. b)



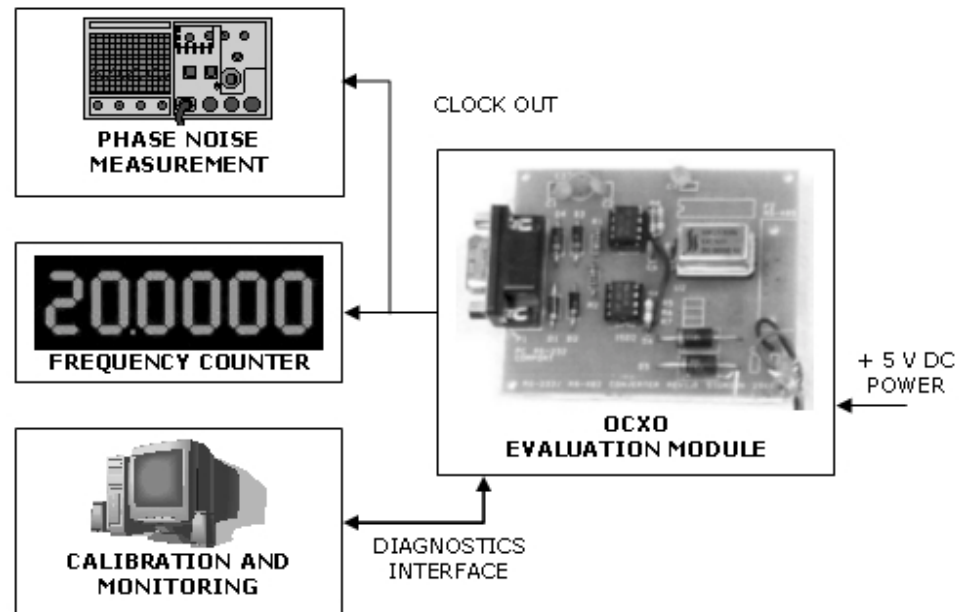
(a) Continually cycling response at 70°C set-point with $K=31$ (b) Oven response: during the settling period, from 0-300 secs, the supply voltage is 5.25V; from 300-420 seconds, the supply voltage is 4.75V; while in the remaining time the supply is once again 5.25V

Temperature set-point and frequency tuning

- Modified Allan variance (for phase noise) is:

$$\text{mod } \sigma_y^2(\tau) = \frac{2}{n^4 \pi^2 \tau_0^2} \int_0^{f_h} \frac{S_y(f) \sin^6(\pi \tau f)}{f^2 \sin^2(\pi \tau_0 f)} df$$

- Rather than specifying Allan variance, it is typical to specify the maximum value of the noise spectrum, S_y , at specified offsets from the center frequency
- Adjust the temperature set-point to obtain lowest phase noise curve
- Adjust the center frequency through the varactor diode bias
- Repeat the previous two steps until desired phase noise and center frequency are obtained



We have described:

- Oven construction
- Oven electronics
- Digital control algorithm
- Oven parameter tuning
- Temperature set-point and frequency tuning

Realizing a high performance and compact OCXO is a function of several other factors (in crystal manufacturing process) that have not been described!